

ABSTRACT

POSITIVE-TYPE PHOTSENSITIVE RESIN COMPOSITION,
METHOD FOR PRODUCING RESIST PATTERN,
SEMICONDUCTOR DEVICE, AND ELECTRONIC DEVICE

5 The positive tone photosensitive composition of the invention comprises an alkali-soluble resin having a phenolic hydroxyl group, a compound producing an acid by light, a thermal crosslinking agent and an acrylic resin. It is possible to provide a positive tone photosensitive composition that can be developed with an aqueous alkali solution, has sufficiently high sensitivity and resolution, and can form a resist pattern with excellent adhesiveness and thermal shock resistance.

Fig. 1